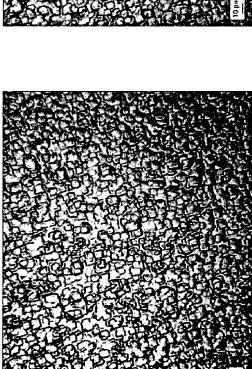
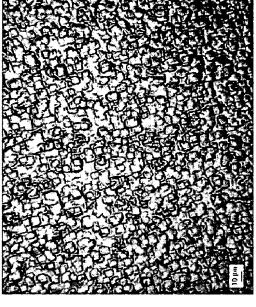
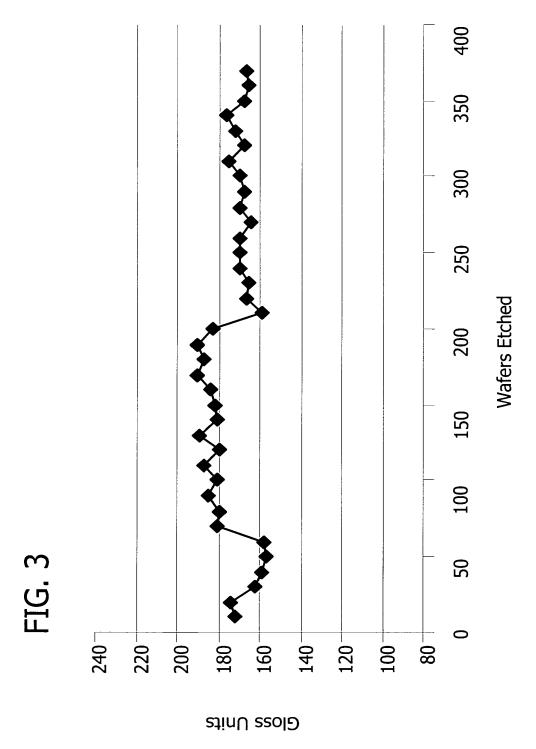
FIG. 1 FIG. 2

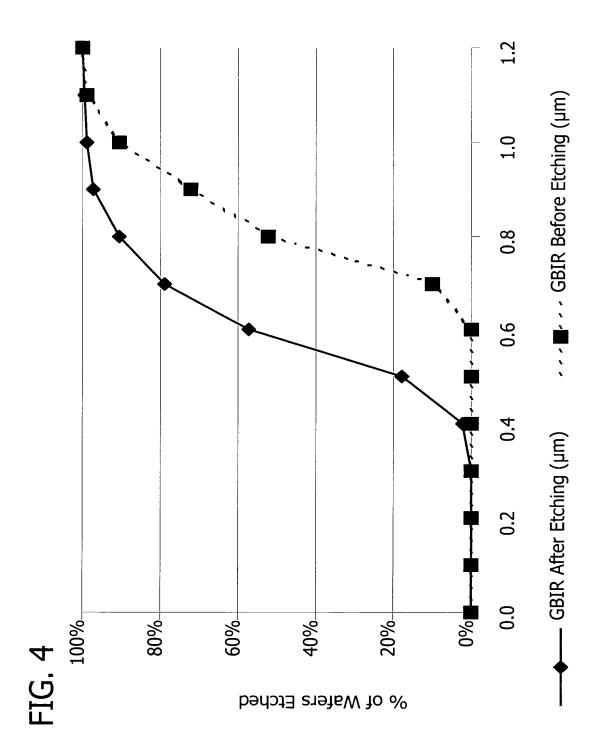




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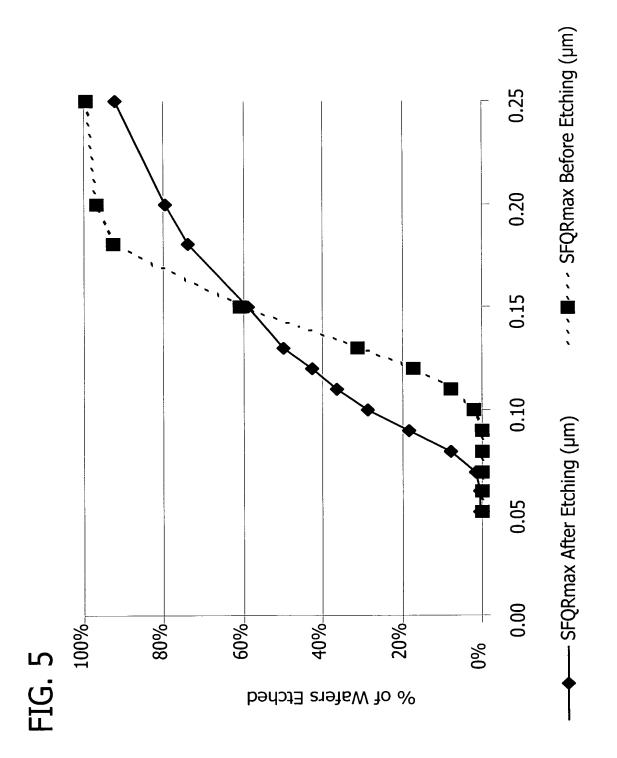


FIG. 6

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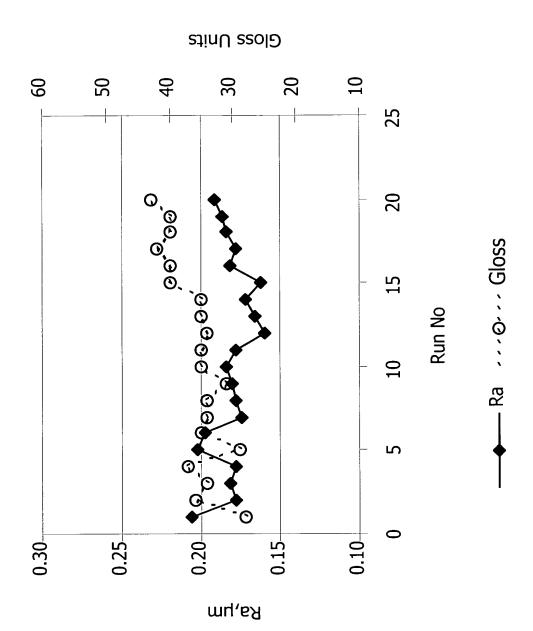
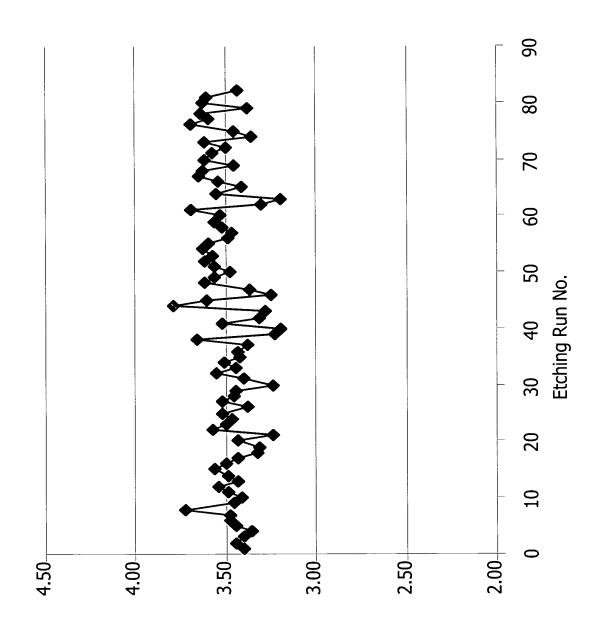
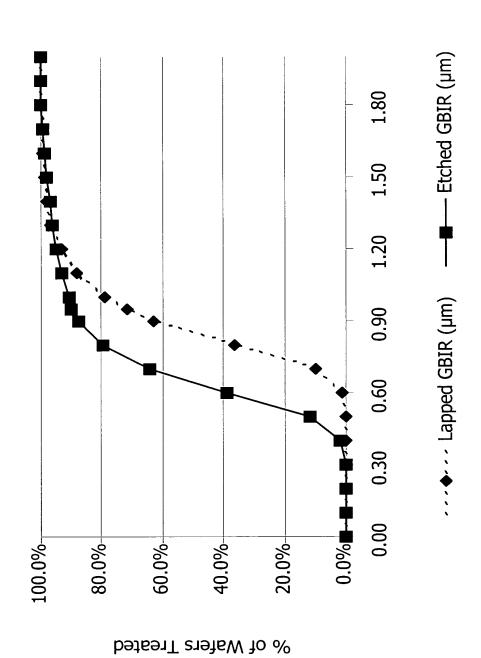


FIG. 7



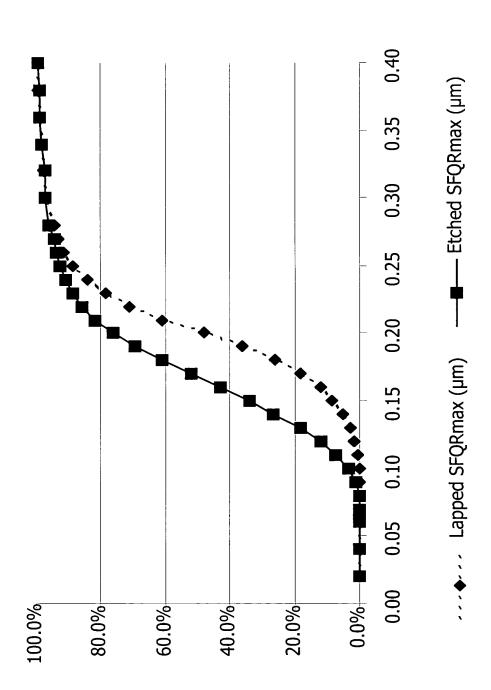
Etching Rate, µm/min







**.**.,



% of Wafers Treated

FIG. 10

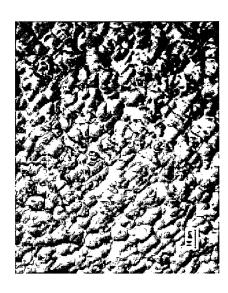
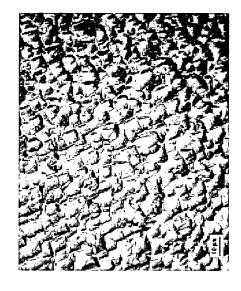




FIG. 12



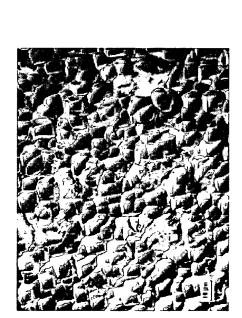
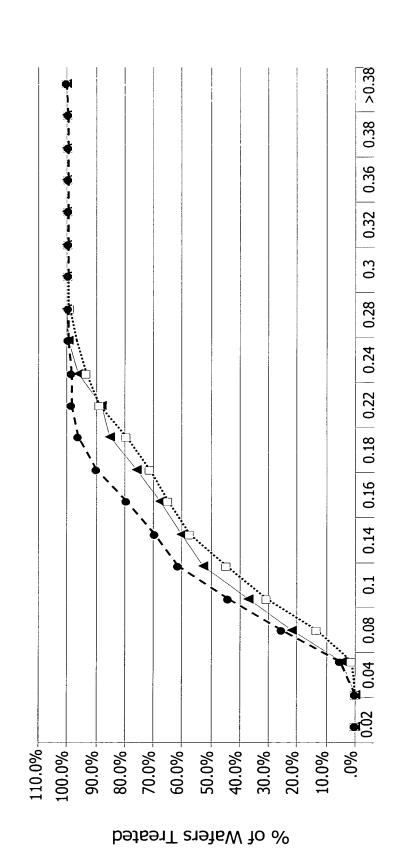


FIG. 14



- Φ- SFQRmax As Buffed (μm)

.....SFQRmax As Etched (µm)

—▲— SFQRmax As Lapped (µm)

FIG. 15

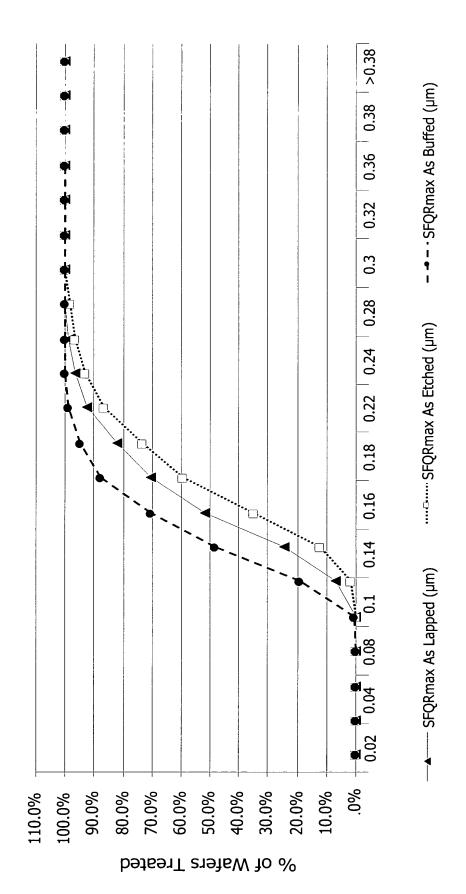
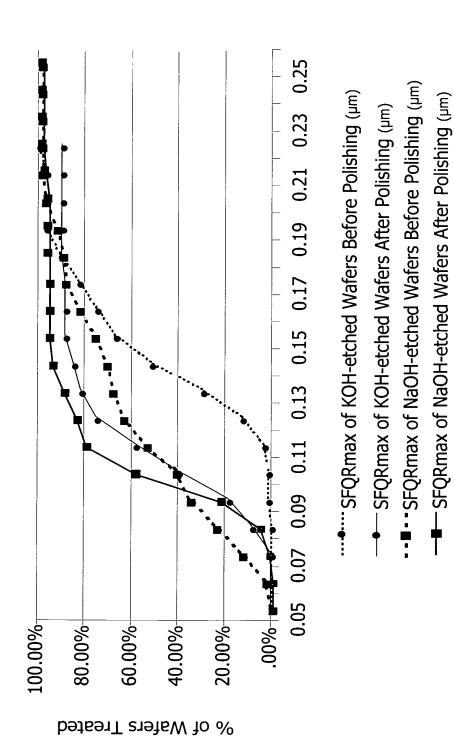
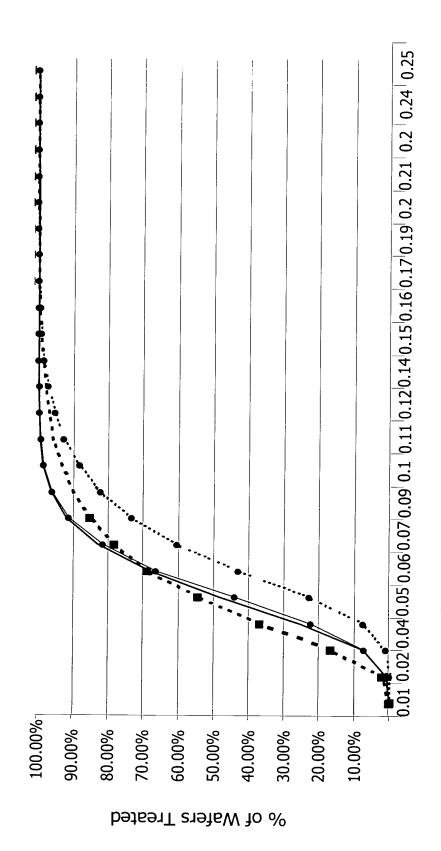


FIG. 16



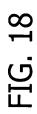
IG. 17



....all-site SFQR of KOH-etched Wafers Before Polishing (µm)

———all-site SFQR of KOH-etched Wafers After Polishing (µm)

••■••all-site SFQR of NaOH-etched Wafers Before Polishing (µm) —■—all-site SFQR of NaOH-etched Wafers After Polishing (µm)



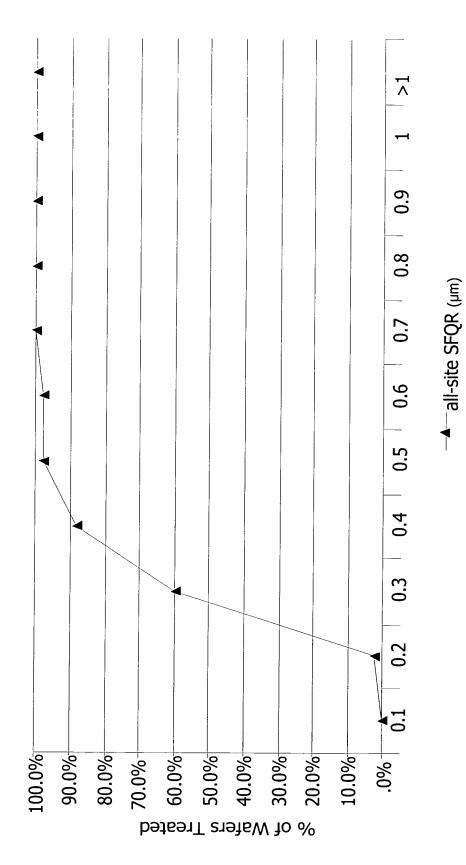


FIG. 19

